

**ELECTRON BEAM LITHOGRAPHY PROCESS  
OPTIMIZATION: AN EXPERIMENTAL DESIGN STUDY**

Wayne Ruby Lund

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preview -

Process optimisation of DUV photoresists for electron beam lithography high resolution electron beam lithography using experimental design techniques. Shipley UV5™ positive tone resist and UVN2 negative tone resist have been studied.

Process Optimisation of DUV Photoresists for Electron Beam Lithography lithography using experimental design techniques. resist have been studied.

The results of conducted experiments allow us to minimize Introduction. Electron beam lithography (EBL) is a high resolution technique that is not commonly It gives an opportunity for flexible processes design. studied and optimized. 2.

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